

LIST OF FIGURES

FIGURE	PAGE	
2.1	The schematic of hard disk drive	4
2.2	(a) Magnetic recording head; (b) Reader and Writer device	5
2.3	Key processes of magnetic recording head fabrication	6
2.4	sp ³ , sp ² and sp ¹ configuration	7
2.5	Ternary diagram, sp ² , sp ³ , and H-Content of ta-C, ta-C: H, a-C:H, and a-C	8
2.6	Schematic of basic subplantation process	10
2.7	Schematic of filter cathodic arc system	10
2.8	Sample of magnetic filter system	12
2.9	Schematic diagram of influences on the Raman spectra	14
2.10	514 nm Raman spectrum of highly orientated graphite	15
2.11	Raman Spectrum of Multi-Wavelength and UV excitation	15
2.12	Dispersion of G peak vs. excitation wavelength, bottom x axis, and energy, top x axis, for a series of template samples	16
2.13	Emission processes of characteristic electrons: (a) a 1s photoelectron ; and (b) KL ₁ L _{2,3} Auger electron	17
2.14	Basic components of a monochromatic XPS system	18
2.15	Wide-scan survey spectrum for all elements	18
2.15	High-resolution spectrum for Si (2p) signal.	19
2.17	XPS depth profile of a SiN/C on NiFe coupon	19
2.18	Reflection of a light beam from a surface showing refraction, reflection and polarization effects	20
2.19	Simple schematic of nanoindenter	21
2.20	SPM image of wear track made on DLC film to determine wear resistance of coating	22
2.21	ScanningWear test on DLC (Diamond like Carbon) coating on a computer hard disk drive with 5 μm, 10 μm and 20 μm loads and 1, 5 and 10 passes respectively	22
2.22	Variation of scanning-scratched wear depth of ta-C and a-C :H films with applied load.	23
2.23	Acid etch corrosion test results for sliders with: (a) no overcoat; (b) ion beam CVD DLC, 5 nm; and (c) FCA coated ta-C, 5 nm.	24
2.24	Example of AFM 3-D images surface roughness of Ti-doped DLC	24
2.25	Raman spectra for a series of anneal temperature up to 900 °C in an ion-beam-sputter-deposited sample	25
2.26	Raman spectra of as-deposited hydrogenated DLC films and annealed films at different temperatures	26
2.27	XPS spectra of C1s; (a) on the original surface of as-deposited hydrogenated DLC; (b) on the worn surface after friction testing in air (RH = 40%)	26
2.28	The dependence of Raman shift on the annealing temperature of (a) as-deposited, (b) annealed at 200 °C, (c) annealed at 300 °C, (d) annealed at 400 °C DLC films.	27
2.29	XPS spectra of the (a) C1s, and (b) O1s core level for annealed Cr-DLC films	27

LIST OF FIGURES (cont.)

FIGURE	PAGE	
2.30	The annealing temperature evolved characters of the Ti-doped DLC films; (a) G-band position and full width at half maximum (FWHM); (b) I_D/I_G ratio	28
2.31	I_D/I_G ratio, G-line width, G peak position, peak intensity of ta-C as a function of annealing temperature.	29
2.32	(a) G-peak position; (b) I_D / I_G vs. annealing temperature for all the samples studied	30
2.33	Raman spectra of ta-DLC(H) as a function of annealing temperature in N ₂ for 1 hr	30
2.34	Internal stress, hardness, friction coefficient and wear rate of the DLC multilayer films before and after anneal.	32
2.35	Wear rates before and after annealing for multilayer films of different soft to hard sublayer ratios.	32
2.36	Slight variation of the measured R_{rms} around 0.2 for the Ti-doped DLC films annealed at various temperatures.	33
2.37	AFM 3-D images of Ti-doped DLC films (a) before annealing and (b) annealed at 600 °C	33
2.38	Evolution of topographic and current images (1x1 mm ²) of ta-C film (carbon ion energy 15 eV) with the increase of annealing temperature.	34
3.1	Schematic diagram of the FCA system for ta-C deposition	36
3.2	Deposition tool image	37
3.3	Deposition tool schematic	37
3.2	Image and Schematic of 514nm Raman System	39
3.3	Image of PHI Quantera II XPS Scanning Microprobe system	39
3.4	Image of Hysitron TriboIndenter	40
3.5	Schematic of Ellipsometry technique and image of system	41
3.6	Determination of unknown value from Ellipsometry model	41
3.7	Image of PANalytical XPert Pro MRD	42
3.8	Image of Atomic Force Microscopy sytem	42
4.1	Raman spectra of the as-deposited ta-DLC films and the annealed films at different temperatures and times; (a) D peak position, (b) G peak position, (c) D peak intensity, (d) G peak intensity, (e) I_D/I_G , (f) FWHM of G peak	43
4.2	Raman parameters of the as-deposited ta-DLC and the annealed films at different temperatures and times.	45
4.3	G position from multi-wavelength Raman of the as-deposited ta-DLC and the annealed films at different temperatures for 60 min.	46
4.4	C1s spectra of the as-deposited ta-DLC and the annealed films at different temperatures and times.	47
4.5	Curve-fitted XPS spectra of C1s of ta-DLC films; (a) as-deposited, (b) after annealing 300 °C for 60 min.	48
4.6	Si2p spectra of the as-deposited ta-DLC and the annealed films at different temperatures and times.	49
4.7	Curve-fitted XPS spectra of Si2p of ta-DLC films; (a) as-deposited, (b) after annealing 300 °C for 60 min.	50
4.8	Wear depth of the as-deposited ta-DLC and the annealed films at different temperatures and times.	51

LIST OF FIGURES (cont.)

FIGURE		PAGE
4.9	Wear images of ta-DLC films; (a) as-deposited; (b) after annealing at 300 °C for 60 min.	52
4.10	Corrosion percentage of DLC films heating at 200 °C and 300 °C at 0, 30, 60, 120, and 180 min	52
4.11	Defect density of ta-DLC films; (a) as-deposited; (b) after annealing at 200 °C for 180 min; (c) after annealing at 300 °C for 180 min	53
4.12	n-value and k-value of the as-deposited ta-DLC and the annealed films at different temperatures for 60 min.	54
4.13	Film density of the as-deposited ta-DLC and the annealed films at different temperatures for 60 min.	55
4.14	Surface roughness of ta-DLC films; (a) as-deposited; (b) after annealing 100 °C for 60 min; (c) after annealing 200 °C for 60 min; (d) after annealing 300 °C for 60 min	56